

Form PTO-1449

INFORMATION DISCLOSURE CITATION
ON AN APPLICATION

DEC 10 2003 (several sheets if necessary)

Docket Number (Sequence)

TSMC-01-1247

Application Number

10/657,505

Applicant

Chi-Ming Wu et al.

Filing Date

09/08/03

Group Art Unit

U.S. PATENT DOCUMENTS

INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JM	5998871	12/7/99	Urabe	257	754	2/20/98
JM	6037252	3/14/00	Hillman et al.	438	637	11/5/97
JM	6203613	3/20/01	Gates et al.	117	104	10/19/99
JM	6270572	8/7/01	Kim et al.	117	93	8/9/99
JM	6468924	10/22/02	Lee et al.	438	763	5/31/01
JM	6174809	1/16/01	Kang et al.	438	682	12/15/98
JM	6399491	6/4/02	Jeon et al.	438	680	4/6/01
JM	6139700	10/31/00	Kang et al.	204	192.17	9/30/98

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portion Pages, Etc.)

JM	Patent Application TSMC-01-1248, Serial # 10/653,852, File Date 09/03/03, assigned to a common assignee, "Method of Multi-Element Compound Deposition by Atomic Layer Deposition for IC Barrier Layer Applications".

EXAMINER

Jennifer M. Kennedy

DATE CONSIDERED

October 20, 2005

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.